



FORM PTO-1449 U.S. Department of Commerce Attorney Docket Number Serial No. Patent and Trademark Office to be assigned 5576-137 LIST OF DOCUMENTS CITED BY APPLICANT (Use several sheets if necessary) Applicants: Satoshi Watanabe Filing Date concurrently herewith 752 U. S. PATENT DOCUMENTS Examiner Document Filing Date Initial Number Date Name Class Subclass if Appropriate 5,569,784 10/29/96 Watanabe et al. 564 430 5,580,695 12/03/96 Murata et al. 430 270.1 5,972,559 10/26/99 Watanabe et al. 430 270.1 6,150,068 11/21/00 Sato et al. 430 270.1 FOREIGN PATENT DOCUMENTS Document Translation Number Date Country Class Subclass Yes | No 5249683 09/28/93 Japan G03F 007/075 X (abstract) 10048814 A 02/20/98 G03F 007/004 Japan X (abstract) 10073912 03/17/98 Japan G03F 001/00 X (abstract) 10133371 05/22/98 G03F Japan 007/029 X (abstract) 10142777 05/29/98 Japan G03F 007/004 X (abstract) 10319581 A 12/04/98 Japan G03F 007/004 X (abstract) OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.) Hinsberg et al., "Fundamental Studies of Airborne Chemical Contamination of Chemically Amplified Resists," Journal of Photopolymer Science and Technology, 6(4): 535-546 (1993). Houlihan et al., "A Study of Resist Outgassing as a Function of Differing Photadditives," Proc. SPIE. 3678: 264-274 (1999). Uetani et al., "Positive ArF Resist with 2EAdMA/GBLMA Resin System," Proc. SPIE, 3678: 510-517

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Chette C. DLT

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Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.